



ABSTRACT

Disclosed are a method and apparatus for chemically polishing a liquid crystal substrate or a pair of liquid crystal glass

5 substrates, which can reduce the thickness and smoothen the surface uniformly by discharging bubbles from a bubble generator. A liquid crystal glass substrate, which has become defective in manufacturing process of liquid crystal display, can be reused regardless of the size of the substrate. The surface of a liquid

10 crystal glass or the outer surface of a pair of liquid crystal glass substrates is polished at a polishing rate of 0.5 to 10 μ m/minute in a chemical polishing liquid accumulation tank filled with a chemical polishing liquid containing a mixed liquid of hydrofluoric acid and fluorinated substances, an inorganic acid, an organic acid, an

15 anionic surfactant, and an amine-type ampholytic surfactant.